



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kiyoichi SUWA

Group Art Unit: 2818

Application No.: 09/729,339

Examiner: Q. Hoang

Filed: December 5, 2000

Docket No.: 108057

For: MASK, EXPOSURE METHOD, LINE WIDTH MEASURING METHOD, AND METHOD
FOR MANUFACTURING SEMICONDUCTOR DEVICES

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed with a Request for Continued Examination. No certification or fee is required.

Respectfully submitted,

Mario A. Costantino
Registration No. 33,565

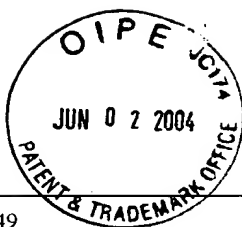
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Date: June 2, 2004

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Sheet 1 of 1

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| Form PTO-1449 (REV. 8-83) | | US Dept. of Commerce PATENT & TRADEMARK OFFICE | | ATTY DOCKET NO. 108057 | | APPLICATION NO. 09/729,339 | |
| INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | | | | APPLICANT(S) Kiyochi SUWA | | | |
| | | | | FILING DATE December 5, 2000 | | GROUP 2818 | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| EXAMINER INITIAL | | DOCUMENT NUMBER | DATE | NAME | CLASS | SUB CLASS | |
| | | 6,296,977 B1 | 10-02-2001 | Kaise et al. | | | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
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| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.) | | | | | | | |
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| EXAMINER | | | | | DATE CONSIDERED | | |
| Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | |

Date: June 2, 2004